

SHIGA7.032APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	HOJO, T et al.
Appl. No.	:	Unknown
Filed	:	Herewith
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN
Examiner	:	Unknown
Group Art Unit	:	Unknown

PRELIMINARY AMENDMENT**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S.

National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Remarks/Arguments begin on page 3 of this paper.